



## **Canon Stepper Specification** **FPA-1550MIVW**

Reticle Size:	□5" (□126.6 mm), 0.09"t (2.3 mm t)
Wafer Size:	4", 5", 6" Capable
Magnification:	X 1/5
Numerical Aperture:	0.55
Image Field:	□20 mm (∅ 28.28 mm)
Printing Wavelength:	g-line (436 nm)
Resolution:	0.60 μm
Illumination Lamp:	1.0 kW super-high-pressure Hg lamp
Illumination Uniformity:	≤1.2 %
Intensity:	≥550mW/cm <sup>2</sup>
Alignment Modes:	TTL On-Axis die-by-die alignment TTL On-Axis global alignment TTL Off-Axis global alignment
Alignment Light Source:	He-Cd laser (442 nm) He-Ne laser (633 nm)
Alignment Accuracy:	≤0.14 μm (mean + 3σ)
Throughput:	≥57 wafers / hour (6", 45 shot)
Wafer Leveling:	Die-by-die tilt Global tilt